Docket No.: 60188-634 **PATENT**

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of : Customer Number: 20277

Masayuki ENDO : Confirmation Number:

Serial No.: : Group Art Unit:

Filed: August 20, 2003 : Examiner:

For: PATTERN FORMATION METHOD

INFORMATION DISCLOSURE STATEMENT

Mail Stop Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Dear Sir:

In accordance with the provisions of 37 C.F.R. 1.56, 1.97 and 1.98, the attention of the Patent and Trademark Office is hereby directed to the documents listed on the attached form PTO-1449. It is respectfully requested that the documents be expressly considered during the prosecution of this application, and that the documents be made of record therein and appear among the "References Cited" on any patent to issue therefrom.

This Information Disclosure Statement is being filed within three months of the U.S. filing date OR before the mailing date of a first Office Action on the merits. No certification or fee is required.

The relevance of "Immersion lithography at 157 nm" is discussed in the present specification.

Serial No.:

Please charge any shortage in fees due in connection with the filing of this paper, including extension of time fees, to Deposit Account 500417 and please credit any excess fees to such deposit account.

Respectfully submitted,

MCDERMOTT, WILL & EMERY

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Date: August 20, 2003

SHEET 1 OF 1

INFORMATION DISCLOSURE CITATION IN AN APPLICATION						ATTY. DOCKET NO. SE 60188-634			SERIAL NO.			
						APPLICANT Endo MASAYUKI, et al.						
(PTO-1449)						FILING DATE August 20, 2003			GROUP			
U.S. PATENT DOCUMENTS												
EXAMINER'S INITIALS	CITE NO.	Document Number Number-Kind Code2 (if known)		Publication Dat MM-DD-YYYY		Name of Patentee or Applicant of Cited Document			d Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear			
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M. Switkes et al., "Immersion lithography at 157 nm", J. Vac. Sci. Technolo., B19(6), (2001), pp. 2353-2356.												
EXAMINER						DATE CONSIDERED						

^{*}EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

1 Applicant's unique citation designation number (optional). 2 Applicant is to place a check mark here if English language Translation is attached.